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| FORM PTO-1449 (Modified) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | | | Attorney Docket No.: 016301-034400US Applicant: Michael Kwan, et al. | | Application No.: 09/648,395 | |
| | | | Filing Date: September 24, 2000 | | Group: 2812 | |
| Reference Designation | | | U.S. PATENT DOCUMENTS | | | Page 1 |
| Examiner Initial | Document No. | Date | Name | Class | Sub-class | Filing Date (If Appropriate) |
| <u>EW</u> AA | 6,030,881 | 2/29/00 | Papasouliotis et al. | 438 | 424 | |
| ___ AB | | | | | | |
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| ___ AD | | | | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | |
| | Document No. | Date | Country | Class | Sub-class | Translation (Yes/No) |
| ___ AM | | | | | | |
| ___ AN | | | | | | |
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| ___ AQ | | | | | | |
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| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | |
| ___ AS | | | | | | |
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| EXAMINER | | | DATE CONSIDERED | | | |

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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| | | | Filing Date: September 24, 2000 | | Group: 1765 | |
| Reference Designation | | | U.S. PATENT DOCUMENTS | | | Page 1 |
| Examiner Initial | Document No. | Date | Name | Class | Sub-class | Filing Date (If Appropriate) |
| <u>Dr</u> AA | 4,468,413 | 08/28/84 | Bachmann | 427 | 39 | |
| <u>Dr</u> AB | 4,851,370 | 07/25/89 | Doklan et al. | 437 | 225 | |
| <u>Dr</u> AC | 4,872,947 | 10/10/89 | Wang et al. | 156 | 643 | |
| <u>Dr</u> AD | 4,892,753 | 01/09/90 | Wang et al. | 427 | 38 | |
| <u>Dr</u> AE | 4,894,352 | 01/16/90 | Lane et al. | 437 | 238 | |
| <u>Dr</u> AF | 4,960,488 | 10/02/90 | Law et al. | 156 | 643 | |
| <u>Dr</u> AG | 5,000,113 | 03/19/91 | Wang et al. | 118 | 723 | |
| <u>Dr</u> AH | 5,013,691 | 05/07/91 | Lory et al. | 437 | 238 | |
| <u>Dr</u> AI | 5,089,442 | 02/18/92 | Olmer | 432 | 235 | |
| <u>Dr</u> AJ | 5,156,881 | 10/20/92 | Okano et al. | 427 | 572 | |
| <u>Dr</u> AK | 5,215,787 | 06/01/93 | Homma | 427 | 248.1 | |
| <u>Dr</u> AL | 5,271,972 | 12/21/93 | Kwok et al. | 427 | 579 | |
| <u>Dr</u> AM | 5,275,977 | 01/04/94 | Otsubo et al. | 437 | 235 | |
| <u>Dr</u> AN | 5,279,865 | 01/18/94 | Chebi et al. | 427 | 574 | |
| <u>Dr</u> AO | 5,288,518 | 02/22/94 | Homma | 427 | 255.1 | |
| <u>Dr</u> AP | 5,302,233 | 04/12/94 | Kim et al. | 156 | 636 | |
| <u>Dr</u> AQ | 5,314,724 | 05/24/94 | Tsukune et al. | 427 | 489 | |
| <u>Dr</u> AR | 5,319,247 | 06/07/94 | Matsuura | 257 | 760 | |
| <u>Dr</u> AS | 5,334,552 | 08/02/94 | Homma | 437 | 195 | |
| <u>Dr</u> AT | 5,385,763 | 01/31/95 | Okano et al. | 427 | 572 | |
| <u>Dr</u> AU | 5,399,529 | 03/21/95 | Homma | 437 | 195 | |
| <u>Dr</u> AV | 5,413,967 | 05/09/95 | Matsuda et al. | 437 | 235 | |
| <u>Dr</u> AW | 5,416,048 | 05/16/95 | Blalock et al. | 437 | 228 | |
| <u>Dr</u> AX | 5,420,075 | 05/30/95 | Homma et al. | 437 | 195 | |
| <u>Dr</u> AY | 5,429,995 | 07/04/95 | Nishiyama et al. | 437 | 238 | |
| <u>Dr</u> AZ | 5,474,589 | 12/12/95 | Ohga et al. | 65 | 397 | |
| <u>Dr</u> BA | 5,563,105 | 10/08/96 | Dobuzinsky et al. | 437 | 240 | |
| <u>Dr</u> BB | 5,571,576 | 11/05/96 | Qian et al. | 427 | 574 | |
| <u>Dr</u> BC | 5,599,740 | 02/04/97 | Jang et al. | 437 | 190 | |
| <u>Dr</u> BD | 5,648,175 | 07/15/97 | Russell et al. | 428 | 472.3 | |
| <u>Dr</u> BE | 5,661,093 | 08/26/97 | Ravi et al. | 438 | 763 | |
| <u>Dr</u> BF | 5,719,085 | 02/17/98 | Moon et al. | 438 | 424 | |
| <u>Dr</u> BG | 5,850,105 | 12/15/98 | Dawson et al. | 257 | 758 | |
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| <u>Dr</u> BI | 5,937,323 | 08/10/99 | Orczyk et al. | 438 | 624 | |
| <u>Dr</u> BJ | 5,939,831 | 08/17/99 | Fong et al. | 315 | 111.21 | |

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| | | | Filing Date: September 24, 2000 | | Group: 1765 | |
| <u>JK</u> BK | 5,944,902 | 08/31/99 | Redeker et al. | 118 | 723 AN | |
| <u>JK</u> BL | 6,136,685 | 10/24/00 | Narwankar et al. | 438 | 624 | |
| <u>JK</u> BM | 08/344,283 | 11/22/94 | Mizuno | | | |
| <u>JK</u> BN | 08/584,042 | 01/06/96 | Rana et al. | | | |
| <u>JK</u> BO | 09/400,338 | 09/21/99 | Xia et al. | | | |
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| | Document No. | Date | Country | Class | Sub-class | Translation (Yes/No) |
| <u>JK</u> BP | WO 92/20833 | 11/26/92 | PCT | C23C | 16/00 | Yes |
| <u>JK</u> BQ | 4-341568 | 11/27/92 | JP | C23 C16 | 40 | No (abstract only) |
| <u>JK</u> BR | 4-239750 | 08/27/92 | JP | H01 L21 | 90 | No (abstract only) |
| <u>JK</u> BS | J6 1276-977-A | 12/06/86 | JP | C23 C16 | 50 | No (abstract only) |
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| <u>JK</u> BT | Usami et al. "Low Dielectric Constant Interlayer Using Fluorine-Doped Silicon Oxide", Jpn. J. Appl. Phys. Vol. 33, January 1994. pp. 408-412. | | | | | |
| <u>JK</u> BU | Lee et al. "Dielectric Planarization Techniques For Narrow Pitch Multilevel Interconnects", VMIC Conference. June 1987. pp. 85-92. | | | | | |
| <u>JK</u> BV | Abraham, "Reactive Facet Tapering of Plasma Oxide For Multilevel Interconnect Applications", VMIC Conference. June 1987. pp. 115-121. | | | | | |
| <u>JK</u> BW | Shapiro et al. "Dual Frequency Plasma CVD Fluorosilicate Glass: Water Absorption And Stability", DUMIC Conference. February 1995. pp. 118-123. | | | | | |
| <u>JK</u> BX | Matsuda et al. "Dual Frequency Plasma CVD Fluorosilicate Glass: Deposition for 0.25 um Interlevel Dielectrics", DUMIC Conference. February 1995. pp. 22-28. | | | | | |
| <u>JK</u> BY | Qian et al. "High Density Plasma Deposition and Deep Submicron Gap Fill with Low Dielectric Constant SiOF Films", California. DUMIC Conference. February 1995. pp. 50-56. | | | | | |
| <u>JK</u> BZ | Fukada et al. "Preparation of SiOF Films with Low Dielectric Constant By ECR Plasma CVD", Japan. DUMIC Conference. February 1995. pp. 43-49. | | | | | |
| <u>JK</u> CA | Laxman, "Low e Dielectrics: CVD Fluorinated Silicon Dioxides", Semiconductor International. May 1995. pp. 71-74. | | | | | |
| <u>JK</u> CB | Hayasaka et al. "High-Quality and Low Dielectric Constant SiO2 CVD Using High Density Plasma", Dry Processing Symposium. Vol. 2. November 1993. pp. 163-168. | | | | | |
| <u>JK</u> CC | Musaka, "Single Step Gap Filling Technology fo Subhalf Micron Metal Spacings on Plasma Enhanced TEOS/O2 Chemical Vapor Deposition System", International Conference on Solid State Devices and Materials. Japan. 1993. pp. 510-512. | | | | | |
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| <u>JK</u> CE | Yu et al. "Step Coverage Study of Peteos Deposition for Intermetal Dielectric Applications", VMIC Conference. June 1990. pp. 166-172. | | | | | |
| <u>JK</u> CF | Chang et al. "Frequency Effects and Properties of Plasma Deposited Fluorinated Silicon Nitride", American Vacuum Society. 1988. pp. 524-532. | | | | | |
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